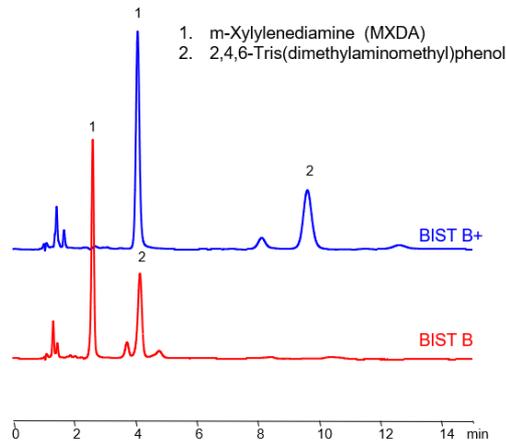


HPLC Method for Separation of Amines on BIST B and BIST B+ Columns



| | |
|----------------------------|---------------------------------------|
| Column: | BIST B , BIST B+ |
| Column size: | 3.2 × 100 mm, 5 µm |
| Column part number: | TBP-32.100.0510 |
| Mobile phase: | MeCN – 70% |
| Buffer: | H ₂ SO ₄ - 0.2% |
| Flow rate: | 0.5 mL/min |
| Detection: | UV 210 nm |

Separation type: Bridge Ion Separation Technology, or BIST™ by SIELC Technologies

m-Xylylenediamine (MXDA) is a popular curing agent used on epoxy resins.

2,4,6-Tris(dimethylaminomethyl)phenol is another amine-based curing agent used on epoxy resins. Using SIELC's newly introduced BIST™ method, these amines can be retained and separated on a positively charged, anion-exchange BIST™ B or BIST™ B+ column. The surface chemistry of BIST™ B+ columns are designed to have stronger ionic retention capabilities, resulting in the marked increase in retention compared to BIST™ B columns.

There are two keys to this retention method: 1) a multi-charged, negative buffer, such as Sulfuric acid (H₂SO₄), which acts as a bridge, linking the positively charged dipeptide to the positively charged column surface and 2) a mobile phase consisting mostly of organic solvent (such as MeCN) to minimize the formation of a solvation layer around the charged analytes. Using this new and unique analysis method, these two amines can be UV detected at 210 nm.

Method Parameters

| | |
|---------------------|---|
| Column | BIST B, 3.2 x 100 mm, 5 µm, 100 Å, dual ended |
| Mobile Phase | MeCN – 70% |
| Buffer | H ₂ SO ₄ – 0.2% |
| Flow Rate | 0.5 mL/min |
| Detection | UV 210 nm |

Quelle: <https://sielc.com/hplc-separation-of-amines-bist>